



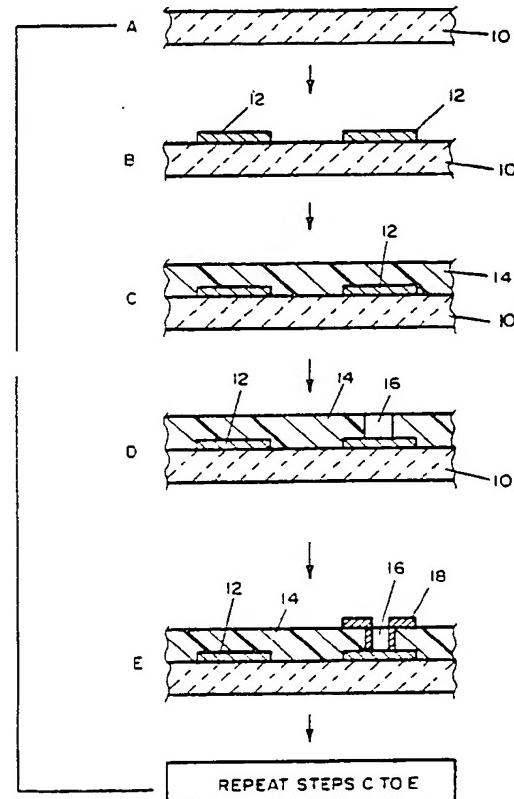
## INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

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## (54) Title: MULTILAYER HYBRID INTEGRATED CIRCUIT

## (57) Abstract

A multilayer circuit device comprises a substrate having a plurality of metallized patterns (e.g., 12, 18) thereon said patterns being separated by a photodefined polymeric dielectric film (14) formed from a polymeric photo-definable triazine base mixture including a photosensitive acrylate moiety. The various circuit patterns are interconnected by means of microvias (16) through the polymeric film or film layers.



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## MULTILAYER HYBRID INTEGRATED CIRCUIT

### TECHNICAL FIELD

This invention relates to multilayer hybrid  
5 integrated circuits having novel dielectric layer employed  
as part of the circuit.

### BACKGROUND OF THE INVENTION

In the evolution of hybrid integrated circuits for  
switching systems and high performance processes as well as  
10 other electronic devices one of the most critical system  
packaging needs is the capability of utilizing effectively  
high I/O pin-out devices with high speed interconnections.  
To meet this goal multilayer ceramic hybrid integrated  
circuits have been developed. However, the currently  
15 available multilayer ceramic circuits require a complex  
manufacturing system and are relatively expensive.  
Consequently, in order to meet the packaging needs of such  
hybrid integrated circuits while retaining quality,  
reliability and performance demands, especially in  
20 conjunction with the use of very large scale integrated  
circuit chips, in a cost competitive package, further  
improvements are necessary.

To meet this goal, I believe that a multilayer  
polymer hybrid integrated circuit configuration is one  
25 approach to solving the problem. The polymer layer must  
act as a dielectric material between layers containing thin  
film circuitry and must meet many other stringent  
requirements including a high  $T_g$ , a high thermal  
stability and hybrid process compatibility. It would also  
30 be preferred if such a polymeric material were  
photodefinable.

### SUMMARY OF THE INVENTION

A multilayer circuit device comprising a substrate  
having a metallized pattern thereon and a plurality of  
35 polymeric dielectric film layers each having a metallized  
circuit pattern thereon with metallized microvias  
interconnecting the metallized patterns of one layer with

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that of at least one other metallized layer thereunder, said polymeric dielectric layer being formed from a photodefinable triazine base mixture including a photosensitive acrylate moiety.

5 BRIEF DESCRIPTION OF THE DRAWINGS

The Figure is a cross-sectional elevational view representing processing steps, A to E, in forming a device in accordance with the invention.

DETAILED DESCRIPTION

10 It should be understood that the novel device as summarized above is suitable for use as a multilayer printed circuit board employing substrates which are commonly used and are well known in the printed circuit board industry. Also, because of the characteristics of  
15 the triazine based dielectric layer employed, the device is especially suited for use in what is known as a multilayer hybrid integrated circuit device generally employing a ceramic substrate.

To meet the requirements of advancing technology  
20 involving hybrid integrated circuits for switching systems and high performance processes, a multilayer hybrid integrated circuit must be capable of employing a high number of I/O pin-out devices with high speed interconnections. Due to the heat developed and the  
25 electrical requirements, minimum requirements for the dielectric material employed to separate conductor layers include a glass transition temperature ( $T_g$ ) of at least 140°C and good thermal stability to about 220°C, a dielectric constant of no greater than 3.5 and preferably,  
30 the material should be capable of being imaged by means of actinic radiation so as to be able to achieve fine line features and an aspect ratio approaching 1. In addition, the dielectric materials must be tough enough to withstand thermal cycling specifications with severe mismatch in  
35 dimensional stability between the ceramic substrates and the dielectric materials; the dielectric must be compatible with typical ceramic resistors and conductors under

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accelerated life testing and the surface of the dielectric must be metallizable so as to form at an adherent circuit pattern thereon. In addition, the dielectric material must have chemical resistance to all chemicals used in further processing steps and should be in a form that can be coated reproducibly and efficiently. The polymeric dielectric material must also have good high voltage breakdown characteristics and be compatible with all other components and materials employed. Preferably, for commercial purposes, good shelf stability and shelf life of the uncured polymer is required. Heretofore, polymeric dielectric materials meeting these requirements were not available.

In accordance with the present invention, a polymeric mixture having a triazine resin as its primary constituent and including a photosensitive acrylate moiety crosslinking agent, can be used to achieve the necessary goals. The acrylate moiety can be on a separate compound or on the triazine itself. More particularly, a suitable polymeric dielectric formulation giving the ranges of its constituents in weight percent is as follows: triazine, 40-65%; rubber resin, 0-30%; an epoxy-acrylate hybrid resin or individual epoxy and acrylate resins totaling from 0-50%; a hardener, 0-12%; a crosslinking agent, 0-8%; a coupling agent, 0-5%; and a photoinitiator, 1/2-3%.

The preferred rubber resins are acrylonitrile butadiene resins. It is preferred that a hybrid epoxy-acrylate resin be employed rather than individual separate epoxy resin and acrylate resin. Such hybrid resin may be epoxy terminated or vinyl terminated. For example, the half acrylate of the diglycidyl ether of bisphenol-A is suitable. A particularly suitable hardener is N-vinylpyrrolidone. Further, a particularly suitable crosslinking agent is trimethylolpropanetriacrylate. Also a particularly suitable coupling agent to enhance the adhesion of the polymeric dielectric material to the underlying material is a silane coupling agent such as

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glycidoxypropyltrimethoxy-silane. Coupling agents, and in particular silane coupling agents, are well known in the art for enhancing adhesion between dissimilar layers. A suitable photoinitiator is 2,2-dimethoxy-2-phenylacetophenone. In addition to the above, one may also add small amounts of pigment, surfactant and copper chelate thermal stabilizer, e.g., copper benzylacetone. Such additives are generally included, if desired, in amounts of up to about 1%.

Generally preferred formulations of the triazine mixture are as follows:

(A) triazine 50-60 weight percent; epoxy acrylate hybrid 20-30 weight percent, hardener 5-12 weight percent, crosslinking agent 2-6 weight percent, coupling agent 2-5 weight percent, photoinitiator 1-3 weight percent; or

(B) triazine 50-60 weight percent; acrylated rubber 10-25 weight percent, epoxy acrylate hybrid 5-15 weight percent, hardener, crosslinking agent and photoinitiator as in (A); or

(C) triazine 50-55 weight percent; acrylated rubber 20-30 weight percent and the remainder of the ingredients as in (B) plus pigment, surfactant and stabilizer up to 1 weight percent.

More specific examples of suitable photodefinable resin mixtures utilized to form the polymeric dielectric are as follows:

EXAMPLE I

	<u>Component</u>	<u>Weight percent</u>
30	Triazine	56%
	Half acrylate of the diglycidyl ether of bisphenol-A (Celanese)	25%
35	N-vinylpyrrolidone	9%

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	Trimethylolpropanetriacrylate	4%
	Glycidoxypropyltrimethoxysilane	4%
5	2-2-dimethoxy-2-phenylacetophenone	2%

EXAMPLE II

	<u>Component</u>	<u>Weight Percent</u>
10	Triazine	52%
	Acrylated acrylonitrile butadiene rubber	16%
15	Half acrylate of the diglycidyl ether of bisphenol-A	9%
	N-vinylpyrrolidone	9%
20	Epoxy propylacrylate	3.5%
	Trimethylolpropanetriacrylate	4%
25	Glycidoxypropyltrimethoxysilane	4.5%
	2,2-dimethoxy-2-phenylacetophenone	2%

EXAMPLE III

The basic formulation of this example is as follows:

	<u>Component</u>	<u>Weight percent</u>
35	Triazine	50%

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	Acrylated acrylonitrile butadiene rubber	26%
5	Half acrylate of the diglycidyl ether of bisphenol-A	9%
	N-vinylpyrrolidone	9%
10	Trimethylolpropanetriacrylate	4%
	Glycidoxypropyltrimethoxysilane	2%

Added to this basic formula is the following:

15	2,2-dimethoxy-2-phenylacetophenone	2%
	Magenta pigment	0.5%
20	Surfactant	0.2%
	Copper benzyl acetonate	0.5%

The various photodefinable triazine resin mixtures  
25 as set above are employed, as previously indicated, in the  
manufacture of multilayer circuit devices such as  
multilayer hybrid integrated circuits. A typical  
multilayer fabrication process is shown with reference to  
FIG. 1 A-E. FIG. 1A shows the bare substrate 10 such as an  
30 alumina ceramic substrate. FIG. 1B is a representation of  
the substrate 10 after a conductor pattern 12 has been  
placed on one surface thereof. This metallized pattern can  
be formed by any of the well known techniques including  
thin film technology, thick film technology, vacuum  
35 evaporation and electroless plating techniques. Further,  
while the layer is shown to be patterned to form a circuit  
one may employ a blanket metallized layer which may be used

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as a ground plane or power plane for the devices to be attached. FIG. 1C depicts the substrate 10 and first metallized layer 12 with a photodefinaible dielectric 14 applied thereover. This dielectric 14 may be applied by 5 any of the well known techniques including screen printing, brushing, spraying, dipping or the like. Subsequent to application of the photodefinaible dielectric 14, as shown in FIG. 1D, the photodefinaible dielectric 14 is subjected to actinic radiation so as to define microvias 16 which, 10 upon development, are formed therethrough. These microvias 16 allow additional metallization 18 as shown in FIG. 1E to form a contact between adjacent metallized layers. In this way, any desired portions of a top metallized layer may be made to electrically contact any lower metallized layer. 15 Steps 1C to 1E can be repeated to build as many levels as needed or desired. Discrete devices such as integrated circuit chips, resistors, capacitors or the like can be mounted such as by surface mounting techniques or any other available techniques known in the art to any of the 20 metallized layers or preferentially to the top layer. Upon completion, a complete hybrid integrated circuit package is formed. In order to achieve a commercially feasible hybrid integrated circuit for high density packaging of integrated circuit devices and a large number of I/O pin counts, the 25 polymeric dielectric material should have the property requirements tabulated hereinbelow. Where, however, the use is not so stringent and a high number of I/O pin counts is not necessary and lower power is to be used, the requirements may be relaxed. The various requirements and 30 the performance of the photodefinaible triazine mixtures as set forth herein with respect to those requirements are given in the table below.

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Specific Material Requirements

<u>5</u>	<u>Parameter</u>	<u>Requirement</u>	<u>Performance</u>
	$T_g$	>130°C	150-190°C
	Thermal stability		
10	Long term	100°C	180°C
	Short term	125°C	210°C
	Spikes	300°C-10-15 sec.	Passes
	Dielectric constant	<4.0	3.4-3.6
15	Resistor compatibility		
	Thin film	Yes	Yes
	Via-resolution	$7.6 \times 10^{-3}$ cm (3 mil) minimum	$7.6 \times 10^{-3}$ cm (3 mil) min.
20	Chemical resistance	Not sensitive to any of the process chemicals	Passes
	Leakage current	<1 micro amp	<1 micro amp
	Thermal cycle	5 cycles 140°C-40°C	Pass
25			
30			

EXAMPLE IV

This example sets forth the essential steps in preparing a multilayer integrated circuit employing one of the novel triazine mixtures as the photosensitive dielectric layer. In accordance with this process, which is just one example of many variations of processes which can be used for preparing a multilayer integrated circuit

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employing the novel photodefinable dielectric, a substrate  
is first sputter metallized to form a very thin base metal  
layer thereon. A photoresist such as Dupont Riston is then  
applied to the surface and the Riston is exposed and  
5 developed so as to form an image of the desired conductor  
pattern thereon. The exposed metallized layer is then  
electroplated such as with copper followed by nickel and  
gold and thereafter the Riston is stripped from the surface  
and the substrate is etched so as to remove the initially  
10 applied sputtered layer. Thereafter the photodefinable  
dielectric triazine mixture is applied to the surface of  
the substrate by any of the known coating techniques, e.g.,  
spray coating and is warmed so as to prevent bubble  
formation. The triazine mixture is then imaged by exposing  
15 to actinic radiation in a desired pattern and then  
developed so as to create microvias in the triazine  
dielectric layer. The dielectric is cured, e.g., by  
heating at temperatures from 100°C to 210°C.  
Preferably, the surface of the dielectric layer is then  
20 treated such as by means of an argon etch so as to enhance  
the adhesion of that surface for subsequent metallization.  
Thereafter a metal layer is sputtered onto the surface of  
the triazine dielectric layer, another layer of Riston is  
applied over the sputtered layer and the Riston is imaged  
25 in a desired pattern and a second metallization layer is  
built up by electroplating techniques. The Riston is  
thereafter stripped such as with methylene chloride and the  
underlying thin sputtered metal layer over which there is  
no electroplate is removed by etching. By this technique,  
30 interconnections between the first and second pattern  
layers of electroplated conductors are made through the  
microvias in the triazine dielectric layer. These steps  
can then be repeated as many times as required to build as  
many layers as is necessary. Also interconnections can be  
35 made between any lower and any upper layer skipping any  
middle layer if desired. Such techniques would be obvious  
to one skilled in the art. Subsequent to completing the

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last layer, circuit devices such as capacitors, resistors and the like can be mounted or formed so as to interconnect with the top conductive layer or pattern. Further, where desired, the pattern may include a ground plane or power 5 plane or both.

The utilization of these materials will also be important in other circuit material applications, such as encapsulants, cover coats and for single polymer layer circuits.

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Claims

1. A multilayer circuit device comprising a substrate having a metallized pattern thereon and a plurality of polymeric dielectric film layers each having a 5 metallized circuit pattern thereon with metallized microvias interconnecting the metallized patterns of one layer with that of at least one other metallized layer thereunder,

CHARACTERIZED IN THAT

10 said polymeric dielectric layer being formed from a photodefinable triazine base mixture including a photosensitive acrylate moiety.

2. The device according to claim 1,

CHARACTERIZED IN THAT

15 the triazine mixture comprises 40 to 65 weight percent triazine, 0 to 30 weight percent rubber resin, 0 to 50 weight percent of a member of a group consisting of an epoxy acrylate hybrid resin and a combination of an epoxy resin and an acrylate resin, 0 to 12 weight percent of a 20 hardener, 0 to 8 weight percent of a crosslinking agent, 0 to 5 weight percent of a coupling agent and 1/2 to 3 weight percent of a photoinitiator.

3. The device according to claim 2,

CHARACTERIZED IN THAT

25 the rubber resin is an acrylonitrile butadiene rubber, the epoxy and acrylate is in the form of a hybrid epoxy-acrylate resin which is carboxy or vinyl terminated and the coupling agent is a silane coupling agent.

4. The device according to claim 3,

30 CHARACTERIZED BY

including N-vinylpyrrolidone as the hardener, and 2,2-dimethoxy-2-phenylacetophenone as the photoinitiator.

5. The device according to claim 2,

CHARACTERIZED BY

35 including a surfactant and a copper chelate thermostabilizer.

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6. The device according to claim 1,  
CHARACTERIZED IN THAT  
the triazine mixture comprises:  
triazine - 50-60 weight percent;  
5 half acrylate of the diglycidyl ether of  
bisphenol-A - 20-30 weight percent;  
N-vinylpyrrolidone - 5-12 weight percent;  
trimethylolpropanetriacrylate - 2-6 weight  
percent;  
10 glycidoxypropyltrimethoxysilane - 2-5 weight  
percent; and  
2,2-dimethoxy-2-phenylacetophenone - 1-3 weight  
percent.
7. The device according to claim 1,  
15 CHARACTERIZED IN THAT  
the triazine mixture comprises:  
triazine - 50-60 weight percent;  
acrylated acrylonitrile butadiene rubber - 10-25  
weight percent;  
20 half acrylate of the diglycidyl ether of  
bisphenol-A - 5-15 weight percent;  
N-vinylpyrrolidone - 5-12 weight percent;  
epoxy propylacrylate - 1-5 weight percent;  
trimethylolpropanetriacrylate - 2-6 weight  
percent;  
25 glycidoxypropyltrimethoxysilane - 2-5 weight  
percent; and  
2,2-dimethoxy-2-phenylacetophenone - 1-3 weight  
percent.
- 30 8. The device according to claim 1,  
CHARACTERIZED IN THAT  
the triazine mixture comprises:  
triazine - 50-55 weight percent;  
acrylated acrylonitrile butadiene rubber - 20-30  
35 weight percent;

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half acrylate of the diglycidyl ether of  
bisphenol-A - 5-15 weight percent;  
N-vinylpyrrolidone - 5-12 weight percent;  
trimethylolpropanetriacrylate - 2-4 weight  
5 percent;  
glycidoxypyropyltrimethoxysilane - 1-5 weight  
percent;  
2,2-dimethoxy-2-phenylacetophenone - 1-3 weight  
percent;  
10 pigment - 0.25-1 weight percent;  
surfactant - 0.1-1 weight percent; and  
stabilizer - 0.2-1 weight percent.

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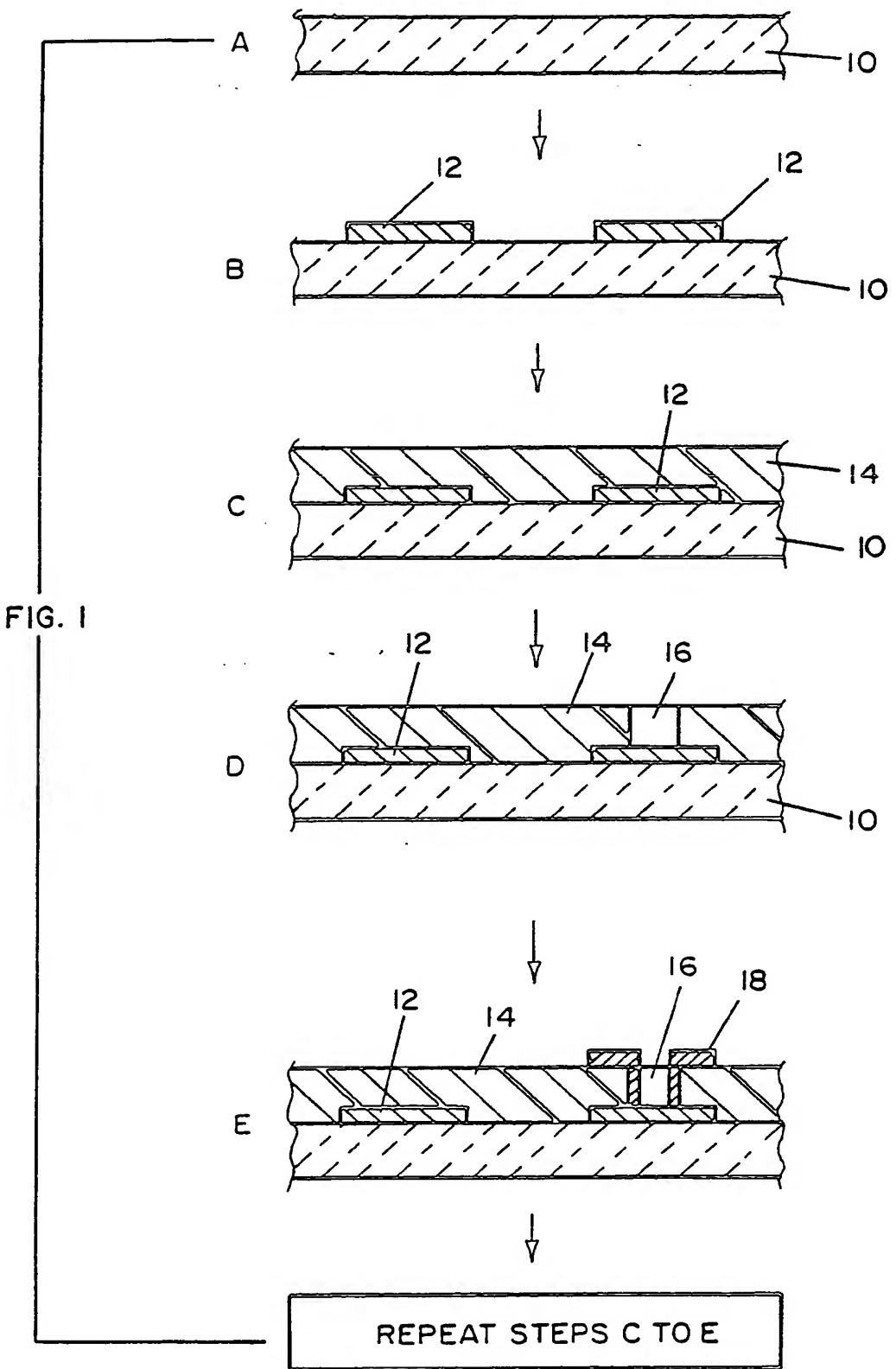
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## INTERNATIONAL SEARCH REPORT

International Application No. PCT/US 85/00422

## I. CLASSIFICATION OF SUBJECT MATTER (if several classification symbols apply, indicate all) \*

According to International Patent Classification (IPC) or to both National Classification and IPC

IPC<sup>4</sup>: H 05 K 3/46; H 01 L 23/52; G 03 C 1/68

## II. FIELDS SEARCHED

Minimum Documentation Searched \*

Classification System	Classification Symbols
IPC <sup>4</sup>	H 05 K
	H 01 L
	G 03 C

Documentation Searched other than Minimum Documentation  
to the Extent that such Documents are Included in the Fields Searched \*

## III. DOCUMENTS CONSIDERED TO BE RELEVANT\*

Category *	Citation of Document, <sup>11</sup> with indication, where appropriate, of the relevant passages <sup>12</sup>	Relevant to Claim No. <sup>13</sup>
A	IBM Technical Disclosure Bulletin, volume 8, nr. 11, (New-York, US) April 1966 M.M. HADDAD: "Additive Multilayer Circuit" page 1482, see page 1482	1
A	EP, A, 0067231 (SONY CORP.) 22 December 1982 see page 12, line 21 - page 13, line 11	1
A	US, A, 3632861 (DOW CHEMICAL CO.) 4 January 1972	
A	Electronic Components, 31 <sup>st</sup> Conference, 11-13 May 1981, (Atlanta, US) J.R. GASKILL et al.: "Kovar Large area Hybrid Module" see page 456 - 464	
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- \* Special categories of cited documents: <sup>10</sup>
- "A" document defining the general state of the art which is not considered to be of particular relevance
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- "G" document member of the same patent family

## IV. CERTIFICATION

Date of the Actual Completion of the International Search

26th June 1985

Date of Mailing of this International Search Report

17 JULY 1985

International Searching Authority

EUROPEAN PATENT OFFICE

Signature of Authorized Officer

G.L.M. Knudsenberg

ANNEX TO THE INTERNATIONAL SEARCH REPORT ON

INTERNATIONAL APPLICATION NO. PCT/US 85/00422 (SA 9154)

This Annex lists the patent family members relating to the patent documents cited in the above-mentioned international search report. The members are as contained in the European Patent Office EDP file on 12/07/85

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Patent document cited in search report	Publication date	Patent family member(s)	Publication date
EP-A- 0067231	22/12/82	NL-A- 8120453 GB-A- 2104297	01/11/82 02/03/83
US-A- 3632861	04/01/72	None	

For more details about this annex :  
see Official Journal of the European Patent Office, No. 12/82